



35th International Symposium on Dry Process

DPS 2013

Call For Papers

In parallel with Asian-European International Conference
on Plasma Surface Engineering (AEPSE2013)

August 29-30, 2013

Ramada Plaza Jeju Hotel, KOREA

Overview

About DPS

Dry Processes are the state-of-the-art technologies leading the way through ultra-high performance in microelectronic devices. This symposium has provided for more than three decades a valuable forum of discussion on science and technology of new developments in this field.

Theme

Dry processes and related technologies from fundamentals to applications.

Topics

- 1) Etching Technology
- 2) Manufacturing Technology(AEC, APC, EES, FDC)
- 3) Surface Reaction and Damage
- 4) Plasma Diagnostics and Monitoring System
- 5) Modeling and Simulation
- 6) Plasma Generation(Equipment/Source)
- 7) CVD/PVD/ALD
- 8) Plasma Processes for 3D Device, FPD, Photovoltaic Devices
- 9) Plasma Processes for new material devices (MRAM, Power, Organic)
- 10) Plasma Processes for Biological and Medical Application, MEMS
- 11) Atmospheric Pressure Plasma and Liquid Plasma
- 12) New Dry Process Concepts

Arranged Session

- * **Advanced Process Technology for Patterning beyond 20 nm Node Era**
- * **Plasma Process for Emerging Non-Volatile Memory Devices**

Paper Submission Deadline: April 26, 2013

Registration Fee

Early registration (before June 30, 2013)

Society member	30,000 JPY
Non-member	35,000 JPY
Student	8,000 JPY

Late registration

Society member	35,000 JPY
Non-member	40,000 JPY
Student	10,000 JPY

The registration fee covers participation to all sessions and the conference proceedings with CD-ROM.

Committee Chairpersons

Organizing Committee Chair: Nobuo Fujiwara (Mitsubishi Electric, Corp.)
Executive Committee Chair: Hirotaka Toyoda (Nagoya University)
Geun Young Yeom (Shugkyunkwan University)
Program Committee Chair: Nobuyuki Negishi (Hitachi, Ltd.)
Publication Committee Chair: Osamu Sakai (Kyoto University)

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<http://www.dry-process.org/2013/>

Sponsors(tentative): DPS 2013 is sponsored by The Japan Society of Applied Physics, in conjunction with The Society of Chemical Engineers, Japan, The Institute of Electrical Engineers of Japan, The Chemical Society of Japan, The Vacuum Society of Japan, The Surface Society of Japan, The Surface Finishing Society of Japan, The Institute of Engineers on Electrical Discharges in Japan, The Institute of Electronics, Information and Communication Engineers of Japan, The Electrochemical Society of Japan, The Japan Society of Plasma Science and Nuclear Fusion Research, The Korean Institute of Surface Engineering, The Korean Vacuum Society, and The Center for Advanced Plasma SurfaceTechnology.